

INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional)

YOR920010104US (4370)

Application Number

Unassigned

Applicant(s)

Steven R. Fox, et al.

Filing Date

Herewith

Group Art Unit

Unassigned

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
RP		6,090,689	07/18/00	Sadana, et al.			
LP		6,043,166	03/28/00	Roitman, et al.			
RP		5,930,643	07/27/99	Sadana, et al.			
		5,589,407	12/31/96	Meyappan, et al.			
		5,519,336	05/21/96	Liu, et al.			
		5,288,650	02/22/94	Sadow			
		5,279,978	01/18/94	See, et al.			
		4,975,126	12/04/90	Margail, et al.			
		4,902,642	02/20/90	Mao, et al.			
		4,786,608	11/22/88	Griffith			
		4,749,660	06/07/88	Short, et al.			

11046 U.S. PTO
09/88467
06/19/01

FOREIGN PATENT DOCUMENTS

REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
RP	JP 63 217657	09/09/88	Japan				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

RP	Wolf, S., "Silicon Processing for the VLSI ERA", Vol. 2: Process Integration, 1990, pp. 72-73
1	White, A.E., et al., "The role of implant temperature in the formation of thin buried oxide layers", BEAM-SOLID INTERACTIONS AND TRANSIENT PROCESSES SYMPOSIUM, BOSTON, MA, USA, 1-4 DEC. 1986, pp. 585-590, XP000922701

EXAMINER Rm Pompey	DATE CONSIDERED 12-22-05
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.